	Application No.	Applicant(s)	
Notice of Allowability	09/938,528	ARITA ET AL.	
	Examiner	Art Unit	····
	David S Blum	2813	
The MAILING DATE of this communication ap All claims being allowable, PROSECUTION ON THE MERITS I herewith (or previously mailed), a Notice of Allowance (PTOL-8 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT of the Office or upon petition by the applicant. See 37 CFR 1.3	S (OR REMAINS) CLOSED in 5) or other appropriate commu RIGHTS. This application is s	this application. If not include inication will be mailed in due	ed course. <b>THIS</b>
<ol> <li>This communication is responsive to <u>11/20/03</u>.</li> <li>The allowed claim(s) is/are <u>1,4 and 5</u>.</li> </ol>			
3. A The drawings filed on 20 November 2003 are accepted to	ov the Examiner		
4. Acknowledgment is made of a claim for foreign priority		or (f).	
a) ⊠ All b) ☐ Some* c) ☐ None . of the:		(/).	
<ol> <li>Certified copies of the priority documents ha</li> </ol>	ve been received.		
2. Certified copies of the priority documents ha	ve been received in Applicatio	n No	
3. Copies of the certified copies of the priority of	locuments have been received	in this national stage applicat	ion from the
International Bureau (PCT Rule 17.2(a)).		,	
* Certified copies not received:			•
5. Acknowledgment is made of a claim for domestic priority reference was included in the first sentence of the specific	under 35 U.S.C. § 119(e) (to a cation or in an Application Dat	a provisional application) since a Sheet. 37 CFR 1.78.	a specific
(a) The translation of the foreign language provisional			
6. Acknowledgment is made of a claim for domestic priority in the first sentence of the specification or in an Application	under 35 U.S.C. §§ 120 and/o on Data Sheet. 37 CFR 1.78.	r 121 since a specific reference	e was included
Applicant has THREE MONTHS FROM THE "MAILING DATE" below. Failure to timely comply will result in ABANDONMENT of	of this communication to file a of this application. THIS THRI	reply complying with the requi	rements noted EXTENDABLE.
7. A SUBSTITUTE OATH OR DECLARATION must be sub INFORMAL PATENT APPLICATION (PTO-152) which gi	mitted. Note the attached EXA	MINER'S AMENDMENT or No declaration is deficient.	OTICE OF
8. CORRECTED DRAWINGS (as "replacement sheets") m	ust be submitted.		
<ul><li>(a) ☐ including changes required by the Notice of Draftspe</li></ul>	rson's Patent Drawing Review	( PTO-948) attached	
1) 🗌 hereto or 2) 🔲 to Paper No			
(b) ☐ including changes required by the proposed drawing	correction filed, which	has been approved by the Ex	aminer.
(c) $\square$ including changes required by the attached Examine	r's Amendment / Comment or	in the Office action of Paper N	lo
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on the the margin according to 37 CFI	e drawings in the front (not the R 1.121(d).	back) of
9.   DEPOSIT OF and/or INFORMATION about the departached Examiner's comment regarding REQUIREMENT FOR	osit of BIOLOGICAL MATE THE DEPOSIT OF BIOLOGIC	RIAL must be submitted. N CAL MATERIAL.	ote the
Attachment(s)			
1☐ Notice of References Cited (PTO-892)	5☐ Notice of Info	rmal Patent Application (PTO-	152)
2 Notice of Draftperson's Patent Drawing Review (PTO-948)		nmary (PTO-413), Paper No. <u>2</u>	<u>0031210</u> .
3 Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No	/ Examiners Ai	mendment/Comment	
4 Examiner's Comment Regarding Requirement for Deposit of Biological Material	8⊠ Examiner's Si 9⊡ Other .	atement of Reasons for Allow	ance

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This action is in response to amendment filed 11/20/03.

## **EXAMINER'S AMENDMENT**

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Donald R. Studebaker on 12/10/03.

The application has been amended as follows:

Replace claim 1 with amended claim 1.

## CLAIM 1

1. A method for manufacturing a semiconductor device, comprising the steps of:

forming, in a semiconductor layer formed on a first insulating film, an element isolation groove extending to the first insulating film;

depositing a second insulating film so as to partially fill the element isolation groove by using a vapor deposition method;

forming an embedded layer on the second insulating film so as to completely fill the element isolation groove; and

forming a third insulating film on the embedded layer,

wherein the step of forming the element isolation groove includes another step of forming at least a pair of element isolation grooves with respect to one element formation region of the semiconductor layer;

in the step of forming the third insulating film, the third insulating film is formed such that the pair of element isolation grooves are continuously covered,

second insulating film and the third insulating film are composed of SiO2

the pair of element isolation grooves sandwich a region other than the element formation region, and

the third insulation region continuously covers the pair of element isolation grooves and the region other than the element formation region in the completed device.

## Reasons for Allowance Subject Matter

- 2. Claims 1 and 4-5 are allowed.
- 3. The following is an examiner's statement of reasons for allowance:

Claim 1 contains the limitation for forming a semiconductor device where an embedded layer is formed on a second insulating layer so that an isolation groove (trench) is filled

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and then a third isolation layer is formed that continuously covers at least two element isolation grooves and the region other than the element formation region (as claimed, a region between two isolation grooves), and remains so in the completed device (support for this is shown on pages 24 (line 24) to 25 (line 8) of the instant specification.). This limitation, in combination with the other limitations of claim 1 is not taught or suggested by the prior art of record. Razouk (US005581110A) forms a third isolation layer is formed and continuously covers over at least two element isolation grooves and the region other than the element formation region, but Razouk etches the third layer back so that it covers only the isolation groove and a small region outside the groove. The layer no longer extends over the non-element formation region. Bajor (US 5,504,033) etches back the third layer so that it also is only a cap over the isolation groove.

Claims 3-4 are allowed as being properly dependent upon allowed claim 1.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to David S. Blum whose telephone number is (703)-306-9168 (after approximately 02/05/04 (7571-272-1687) and e-mail address is <a href="mailto:David.blum@USPTO.gov">David.blum@USPTO.gov</a>.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr., can be reached at (703)-308-4940. Our facsimile number all patent correspondence to be entered into an application is (703) 872-9306. The facsimile number for customer service is (703)-872-9317. Our receptionist's number is (703)-308-0956.

David S. Blum

December 12, 2003

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